

FIG. 1A

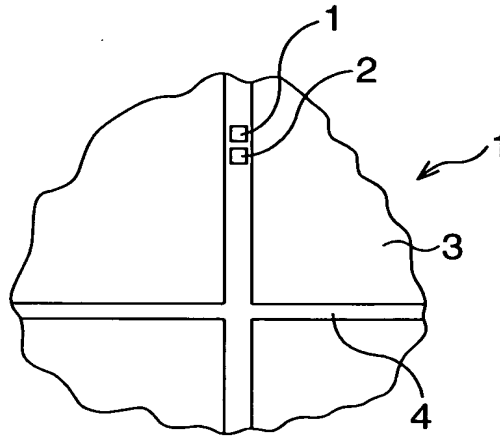


FIG. 1B

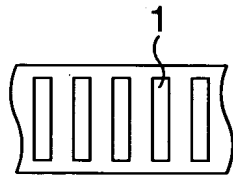


FIG. 1C

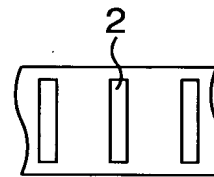


FIG. 2

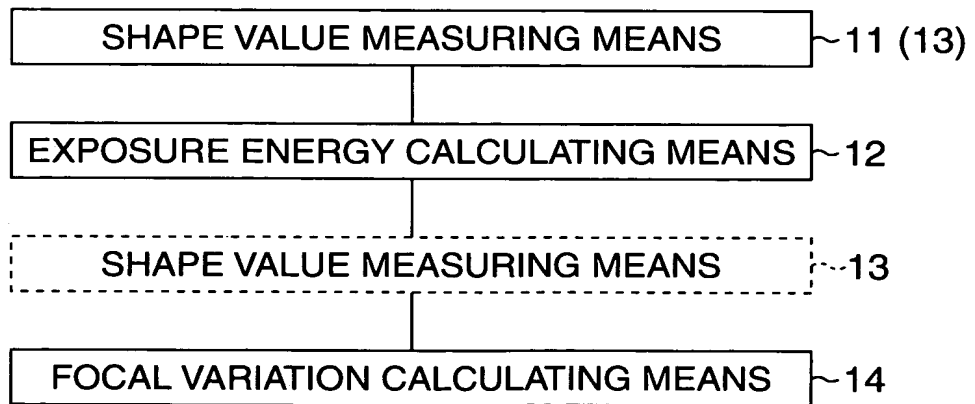


FIG. 3

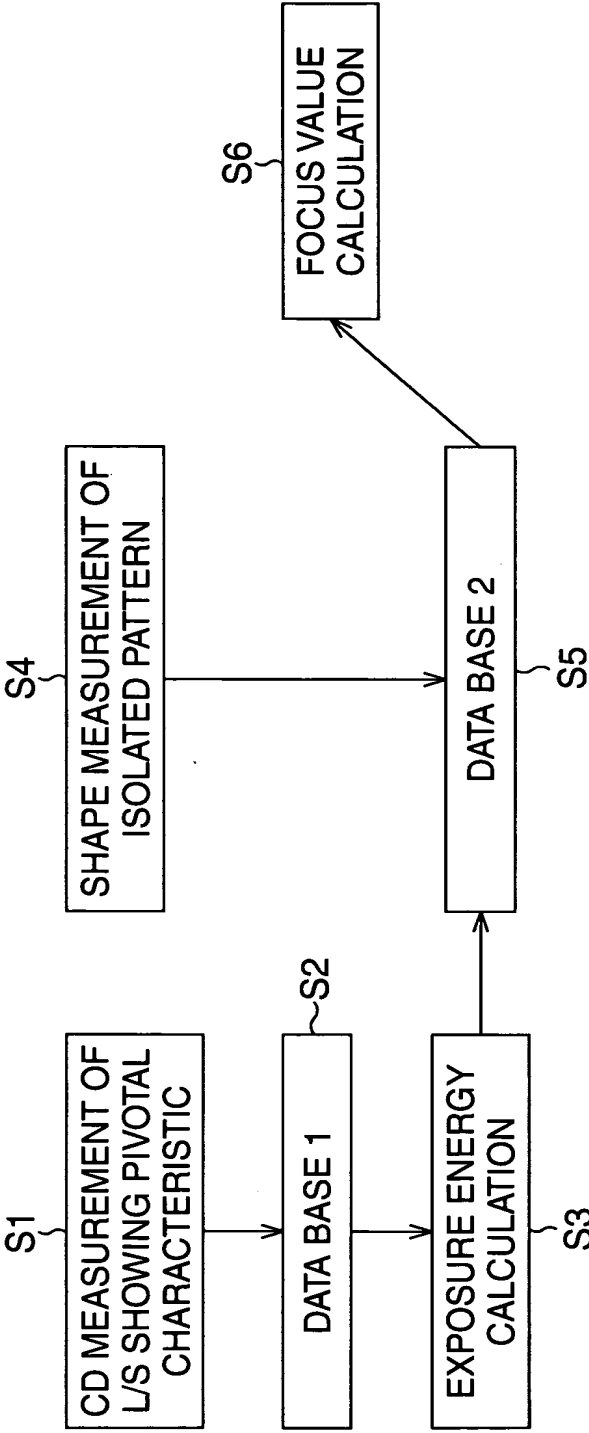


FIG. 4A

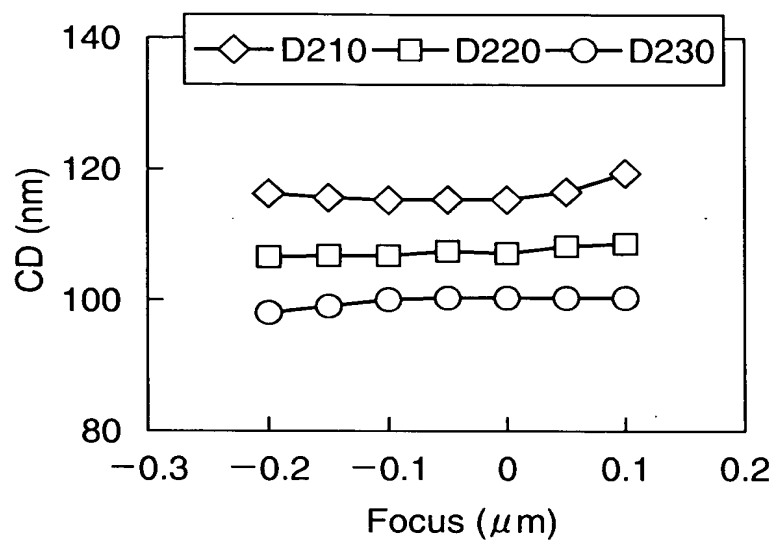


FIG. 4B

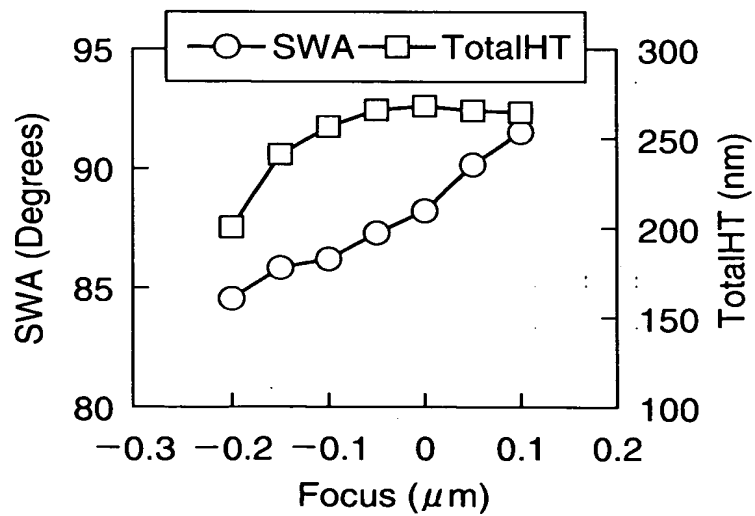


FIG. 5A

1:1 L/S	Dose=194J	Dose=196J	Dose=198J	Dose=200J	Dose=202J	Dose=204J	Dose=206J
CD	126nm	124nm	122nm	120nm	118nm	116nm	114nm
Angle	88°	88°	88°	88°	88°	88°	88°

FIG. 5B

ISOLATED LINE	Focus = -0.06	Focus = -0.04	Focus = -0.02	Focus = 0.00	Focus = 0.02	Focus = 0.04	Focus = 0.06
198J	85.2°	85.4°	85.6°	85.8°	86.0°	86.2°	86.4°
200J	85.4°	85.6°	85.8°	86.0°	86.2°	86.4°	86.6°
202J	85.6°	85.8°	86.0°	86.2°	86.4°	86.6°	86.8°
204J	85.8°	86.0°	86.2°	86.4°	86.6°	86.8°	87.0°

FIG. 6

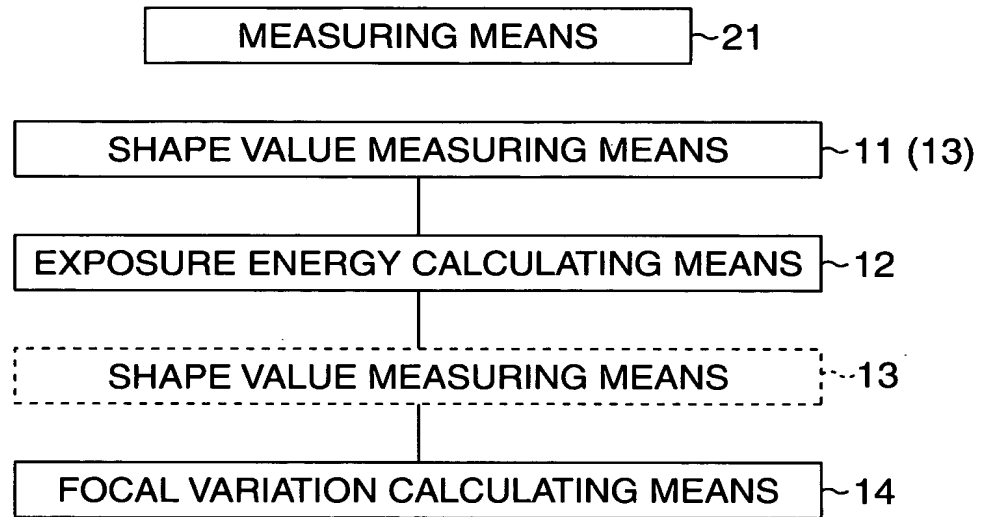


FIG. 7A

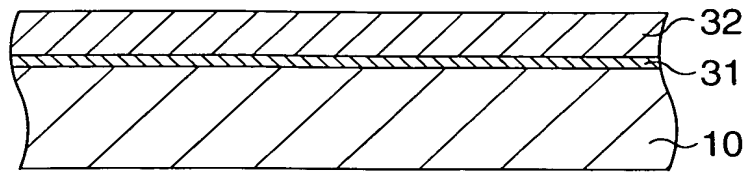


FIG. 7B

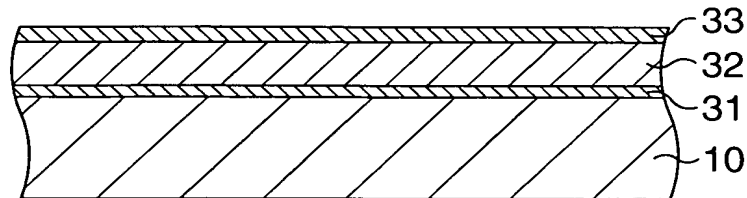


FIG. 7C

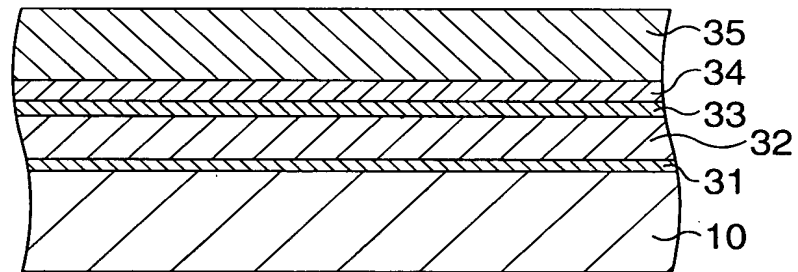


FIG. 7D

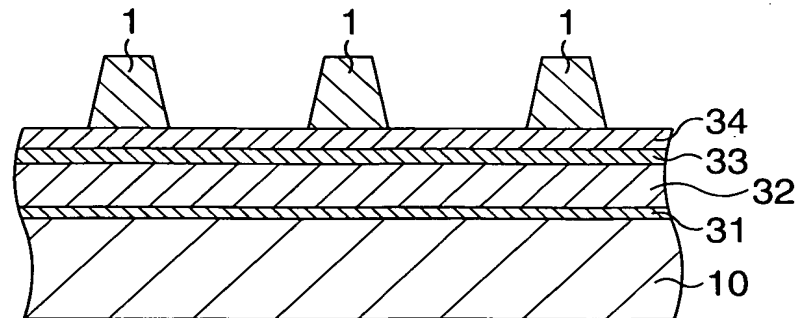


FIG. 8A

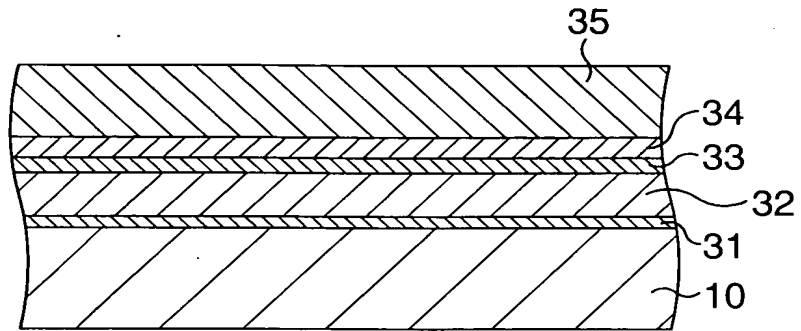


FIG. 8B

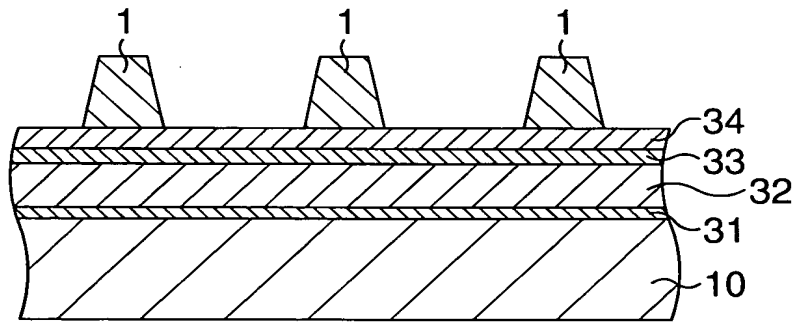


FIG. 9

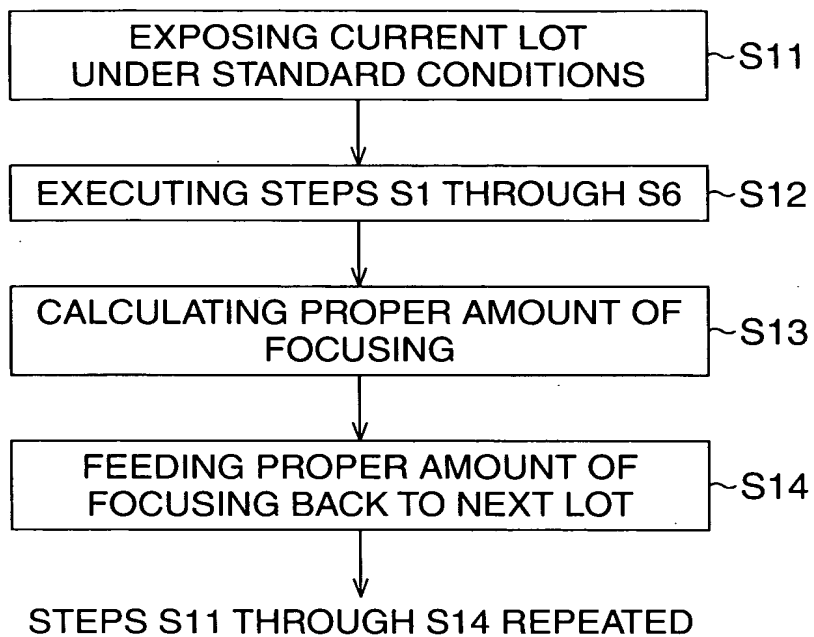


FIG. 10

	RESIST PATTERN FORMATION	MEASUREMENT OF DEFOCUSING
LOT A	FOCUSING CONDITION: STANDARD	DEFOCUSING: $0.04\mu\text{m}$
LOT B	FOCUSING CONDITION: STANDARD $-0.04\mu\text{m}$	DEFOCUSING: $-0.01\mu\text{m}$
LOT C	FOCUSING CONDITION: STANDARD $-0.03\mu\text{m}$	DEFOCUSING: $0.0\mu\text{m}$
LOT D	FOCUSING CONDITION: STANDARD $-0.03\mu\text{m}$	DEFOCUSING: $-0.01\mu\text{m}$
LOT E	FOCUSING CONDITION: STANDARD $-0.02\mu\text{m}$	DEFOCUSING: $0.0\mu\text{m}$
...

FIG. 11

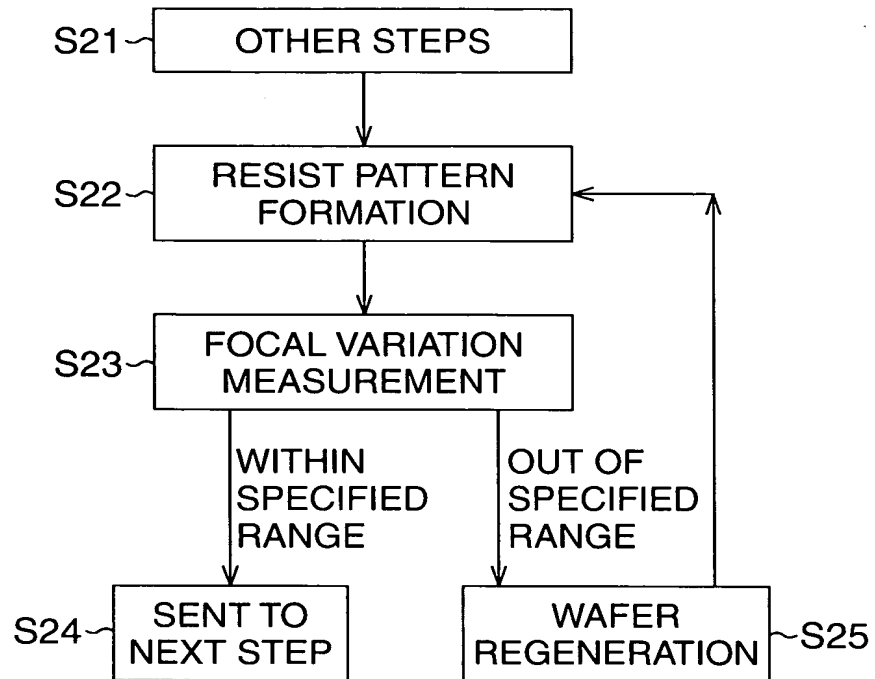


FIG. 12

